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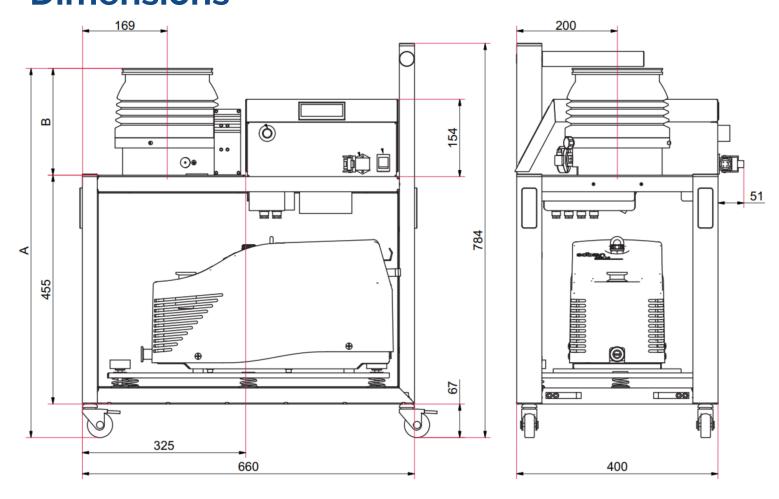
## Pfeiffer HiCube 400 Pro Technical Specifications

Pumping station		HiCube 400 Pro	
Flange (in)		DN 100 ISO-K	DN 100 CF-F
Pumping speed for Nitrogen N <sub>2</sub>	l/s	355	355
Ultimate pressure			
with Piston pump XtraDry 150	mbar	< 1 · 10 <sup>-7</sup>	< 5 · 10 <sup>-10</sup>
with Rotary vane pump PentaLine	mbar	< 1 · 10-7	< 5 · 10 <sup>-10</sup>
Pumping speed backing pump at 50 Hz			
Piston pump XtraDry 150	m³/h	7.5	7.5
Rotary vane pump Penta 10	m³/h	11	11
Rotary vane pump Penta 20	m³/h	22	22
Rotary vane pump Penta 35	m³/h	34	34
Weight pumping station:1)			
with Piston pump XtraDry 150	kg	79.4	85.3
with Rotary vane pump Penta 10	kg	91.4	97.3
with Rotary vane pump Penta 20	kg	92.4	98.3
with Rotary vane pump Penta 35	kg	94.4	100.3
Power consumption			
with Piston pump XtraDry 150	W	970	970
with Rotary vane pump Penta 10	W	975	975
with Rotary vane pump Penta 20	W	1410	1410
with Rotary vane pump Penta 35	W	1895	1895

Ultimate pressure in a measuring dome 48 hours after bake-out, can be attained only with metallic seal of the high vacuum flange. (Ultimate pressure with elastomer seal (standard, not bakeable):  $< 1 \cdot 10^{-7}$  mbar.)

1) without fore-vacuum safety valve

## Pfeiffer HiCube 400 Pro **Dimensions**



Dimensions	HiCube 400 Pro	HiCube 400 Pro
Flange	DN 100 ISO-K	DN 100 CF-F
A	760 mm	760 mm
В	239 mm	239 mm

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## Pfeiffer HiCube 400 Pro **Features & Benefits**

- especially characterized by its extremely fast pump-down times
- features connectivity for digital pressure sensors
- optimal combination of HiPace turbo pump & backing pump
- modular design affords simple customization for application
- service friendly due to accessibility of individual components
- integrated drive electronics
- easy data collection & analysis
- plug & play no installation or cabling required
- · robust engineering makes for long service life
- · optional forevacuum safety valve prevents venting in power failure
- direct connection of vacuum gauges possible

## **Applications**

- research & development accelerators analysis & surface physics
- vacuum process technology
   general vacuum applications

